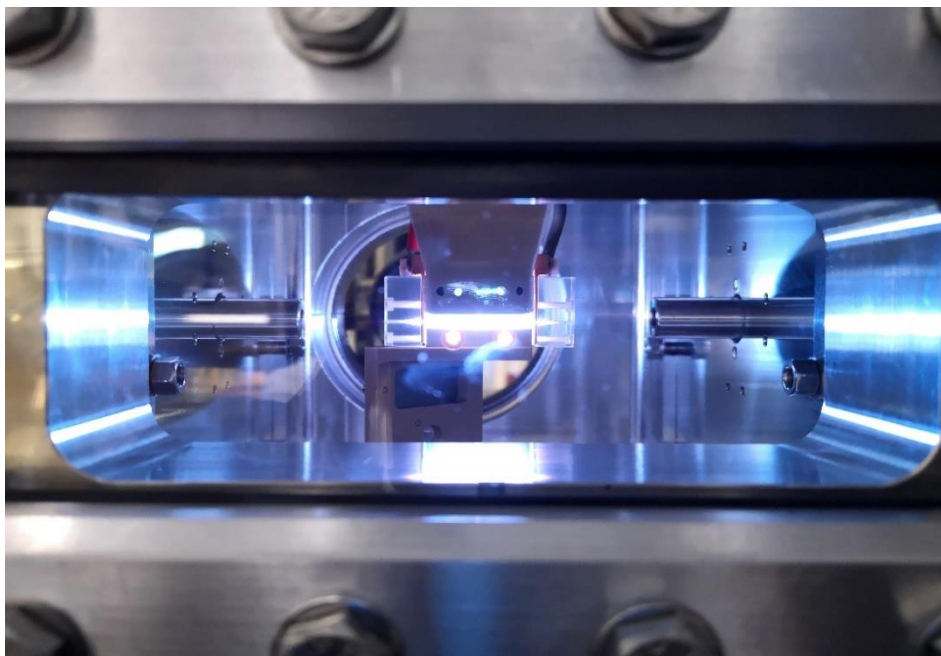


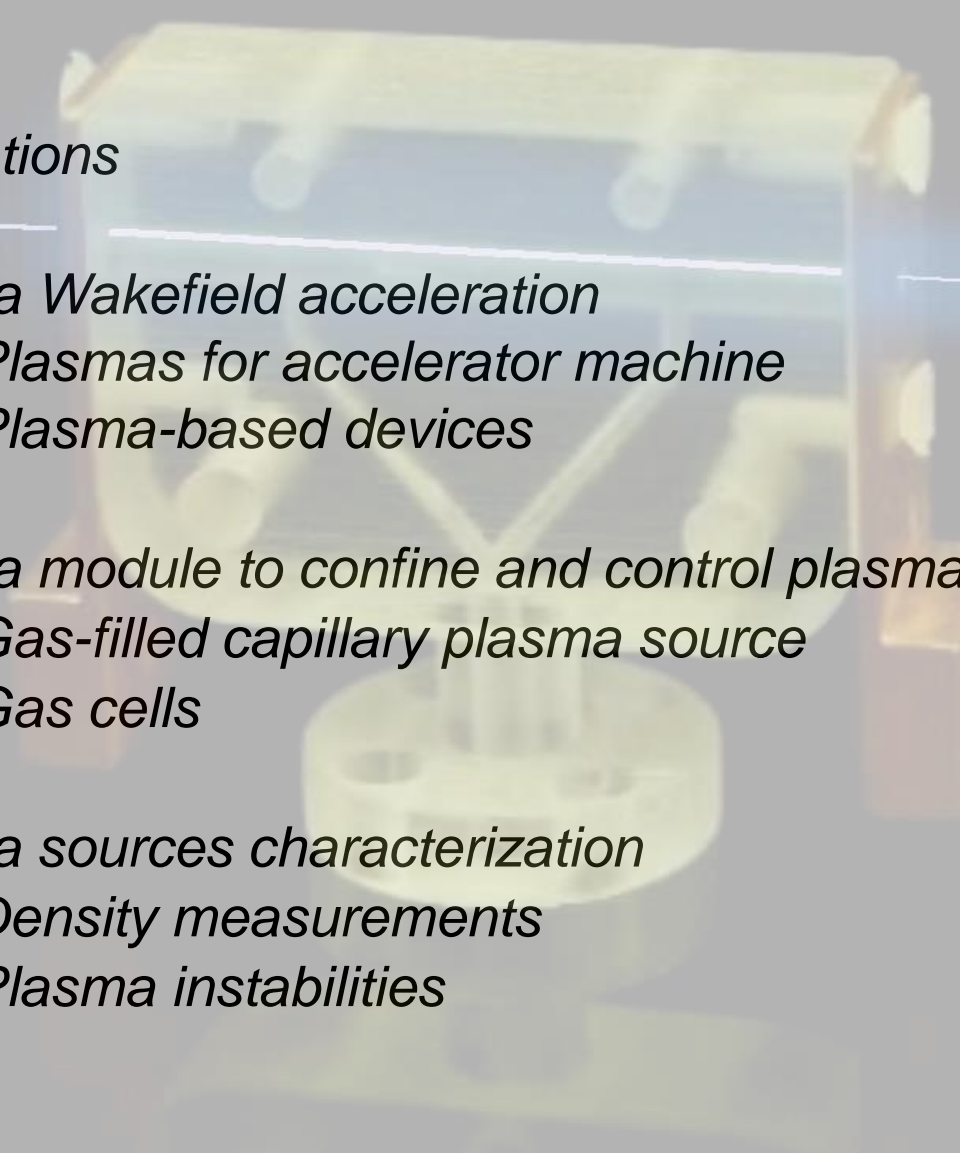
# *Plasma sources design for plasma-based accelerators*

A. Biagioni

*Laboratori Nazionali di Frascati INFN*

*17-18<sup>th</sup> April 2023*



- 
- *Motivations*
  - *Plasma Wakefield acceleration*  
*Plasmas for accelerator machine*  
*Plasma-based devices*
  - *Plasma module to confine and control plasmas*  
*Gas-filled capillary plasma source*  
*Gas cells*
  - *Plasma sources characterization*  
*Density measurements*  
*Plasma instabilities*

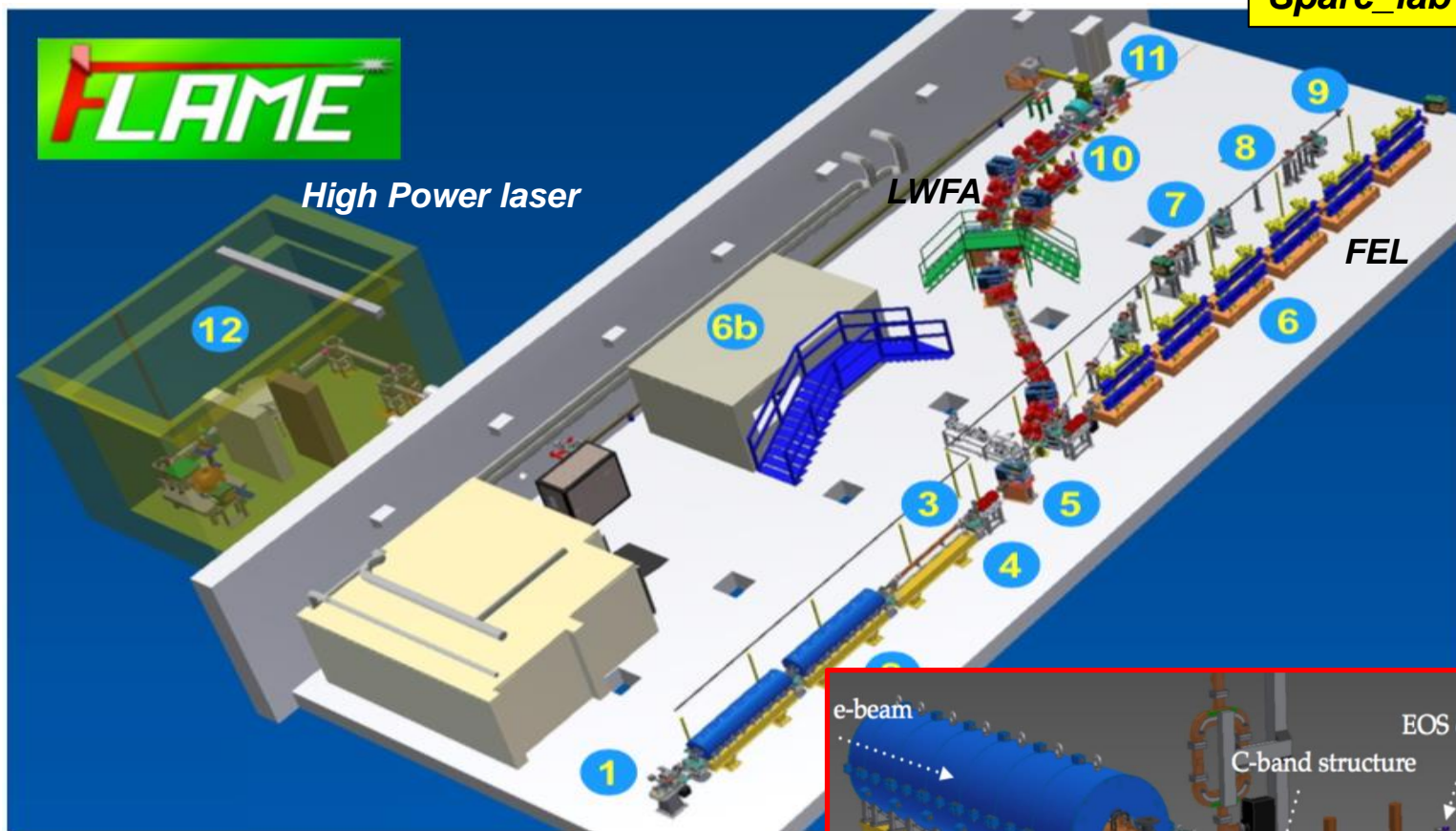
## Sparc\_lab test facility



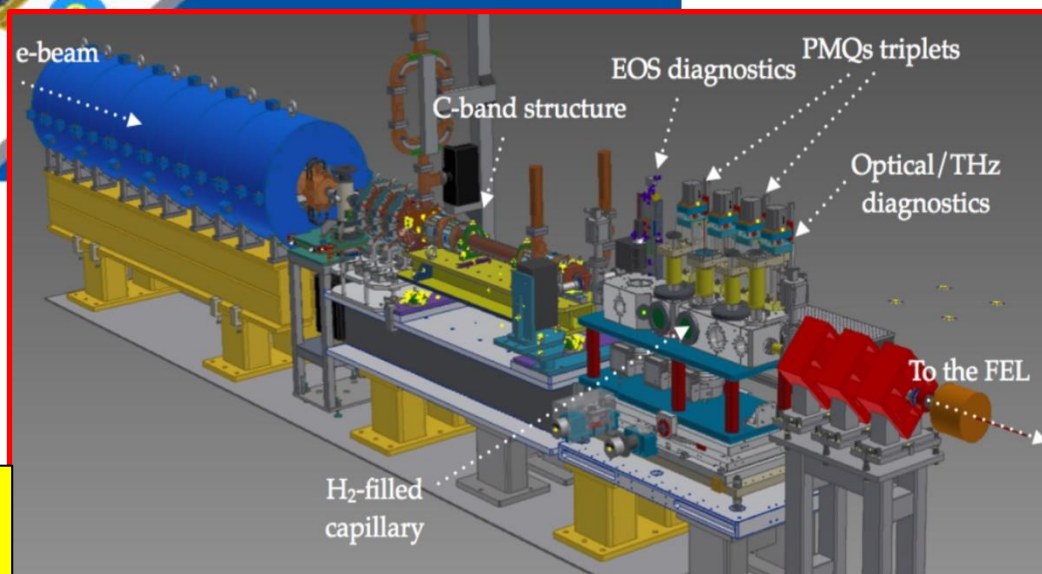
High Power laser

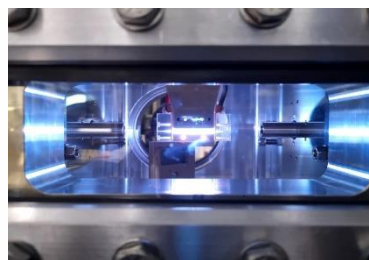
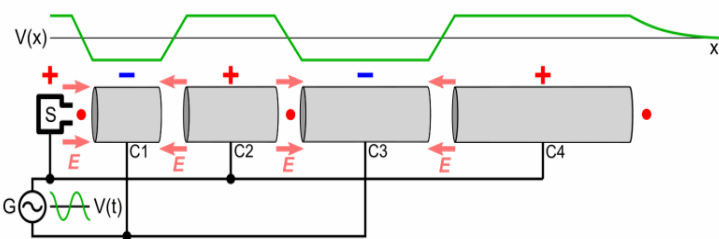
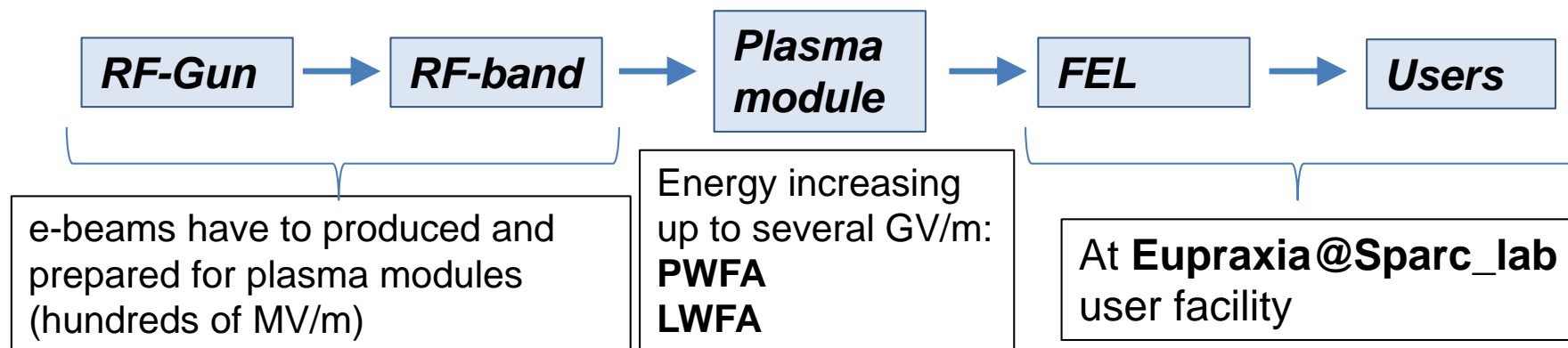
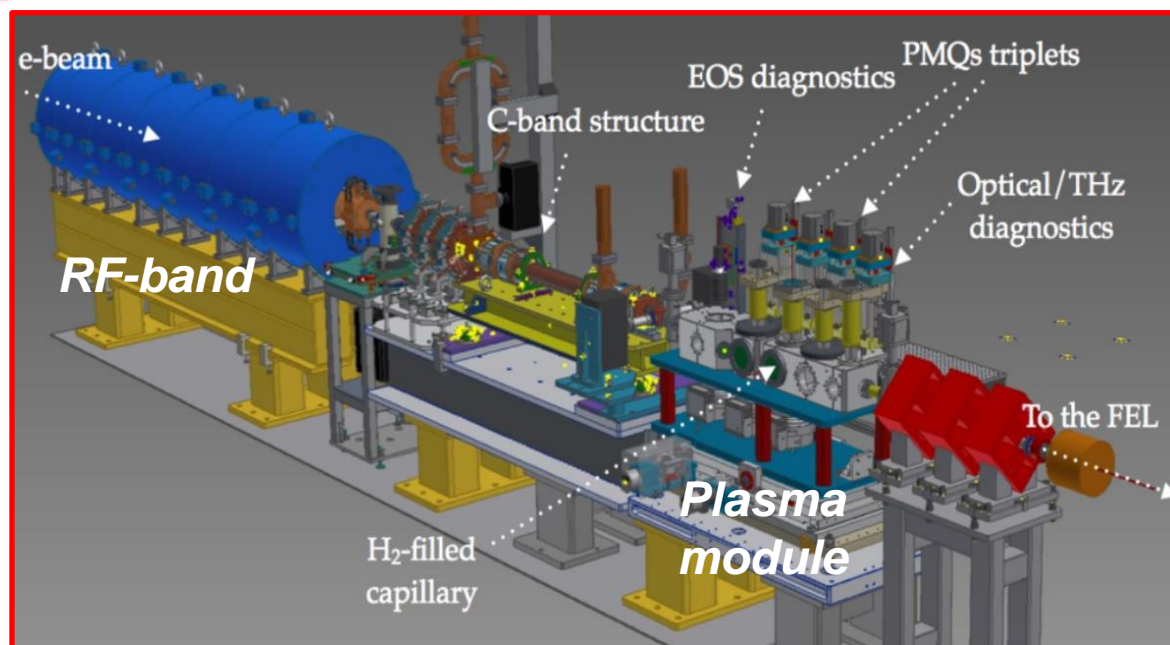
LWFA

FEL



- **Compactness**
- **Accelerating gradient**

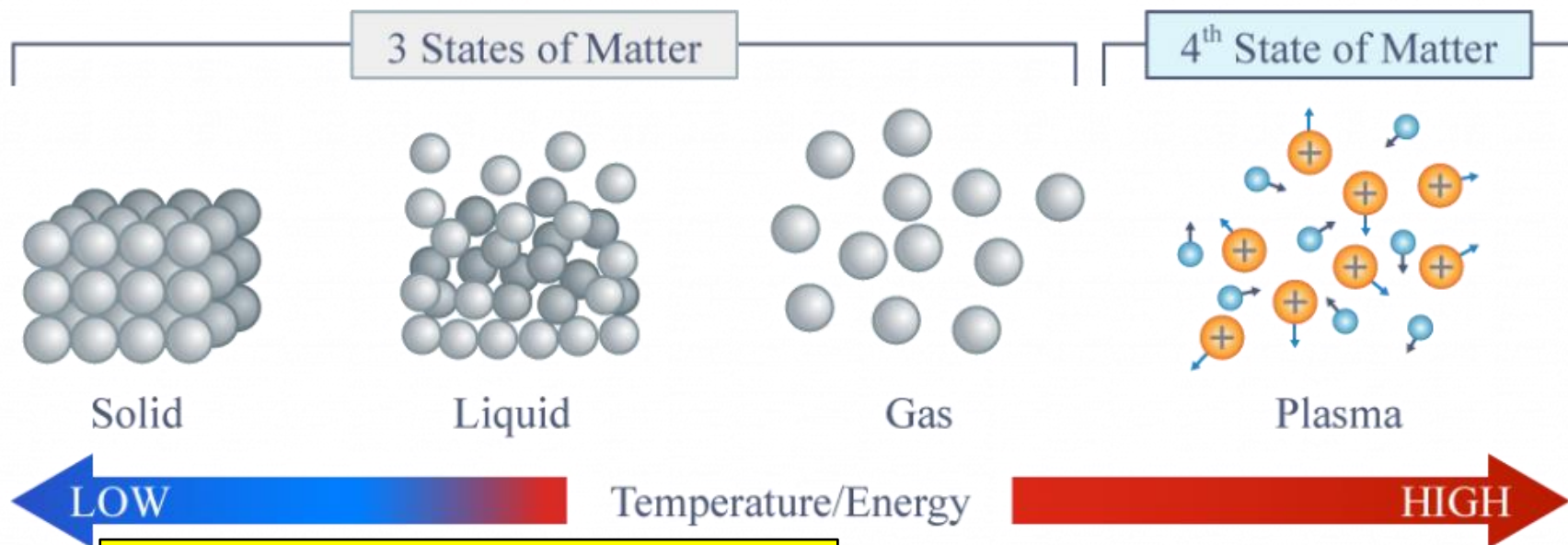
S-band accelerating structures: **20 MV/m**C-band accelerating structures: **35 MV/m**Up to **10-100 GV/m** for Plasma-based accelerating structures





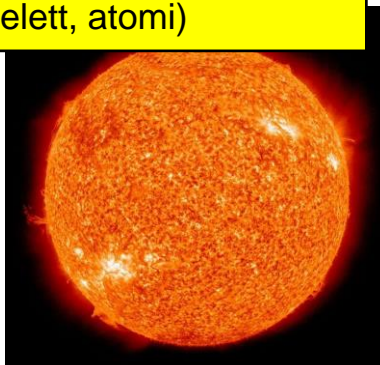


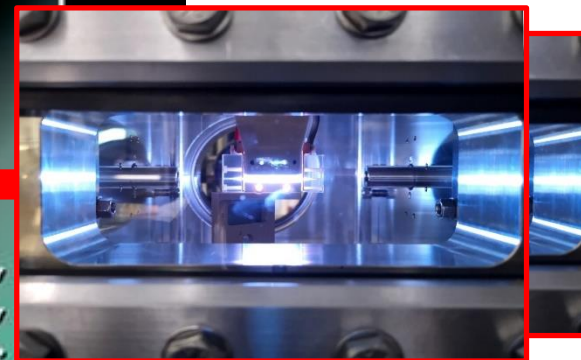
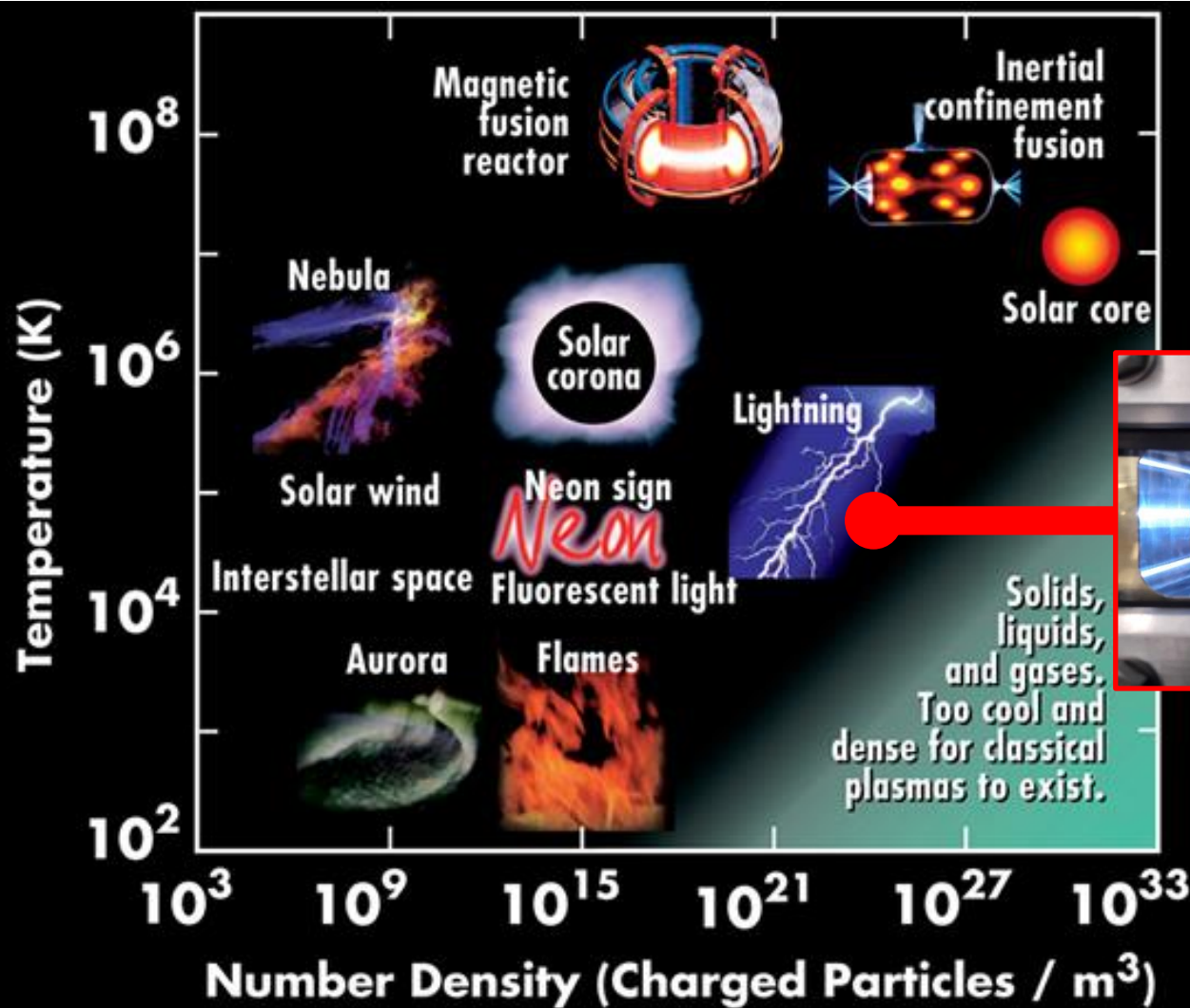
# Plasma wakefield acceleration



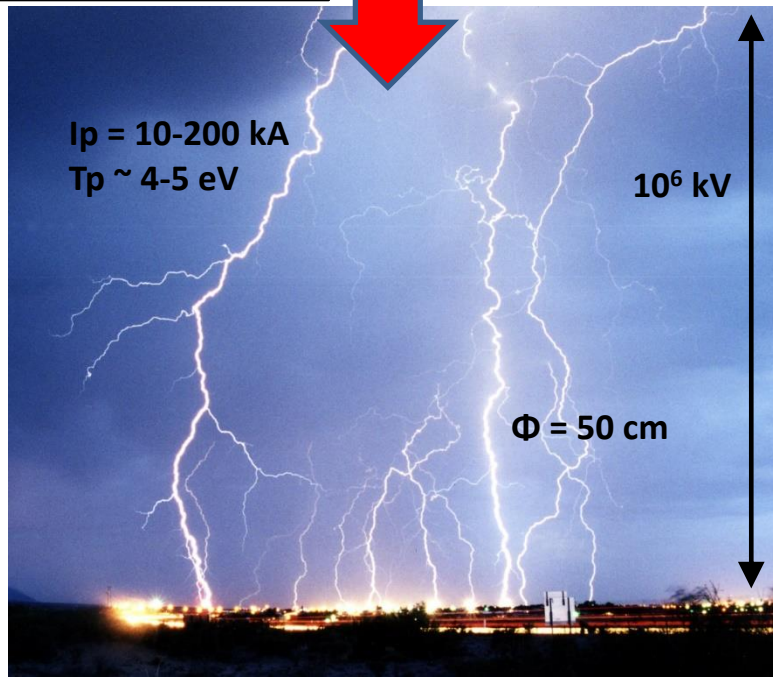
## Confinamento e formazione del Plasma

- Breve durata (decine di microsecondi)
- Instabilità
- Alte temperature
- Disuniformità
- Equilibrio termodinamico tra particelle di diverso tipo (ioni, elett, atomi)

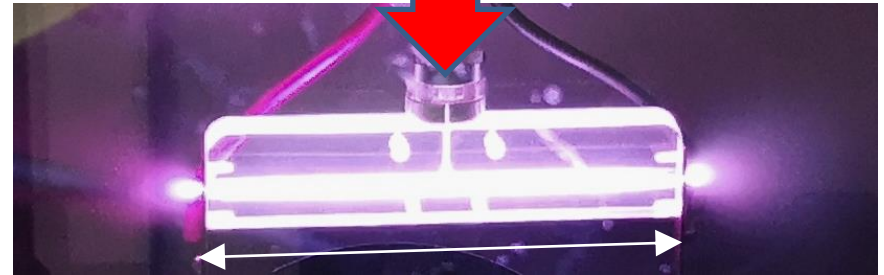




## Natural plasmas



## Artificial plasmas



$I_p = 0.3 - 1 \text{ kA}$   
 $T_p \sim 2-10 \text{ eV}$   
 $V_p = 5-20 \text{ kV}$   
 $\Phi = 1-2 \text{ mm}$

$$T_e(0) \approx 5.7 \left( \frac{I_{\text{peak}} [\text{kA}]}{r_{\text{cap}} [\text{mm}]} \right)^{2/5} \text{ eV}$$

$$T_{\text{lightning}} \sim 4 \text{ eV}$$

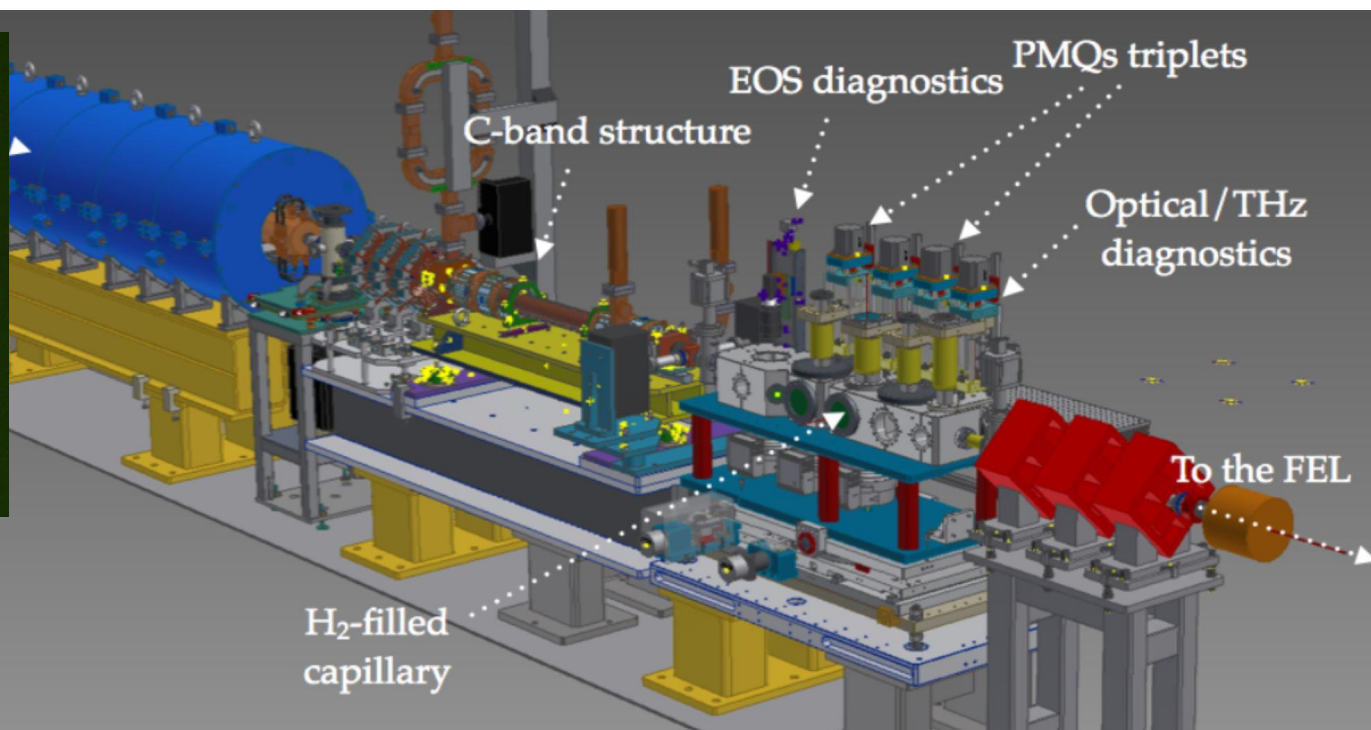
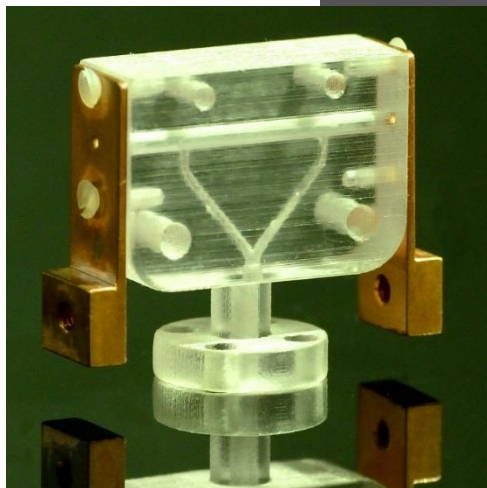
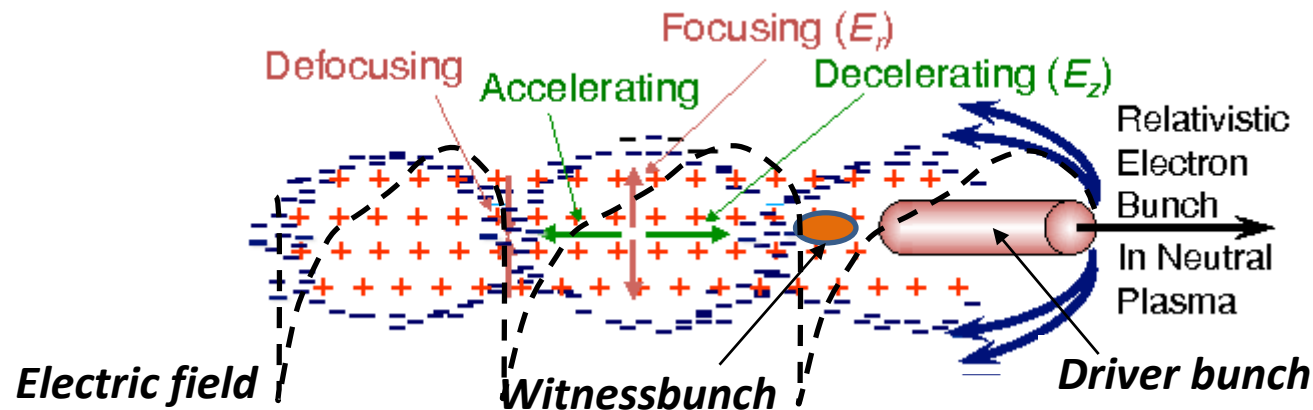
$$T_{\text{plasma source}} \sim 5.7 \text{ eV}$$

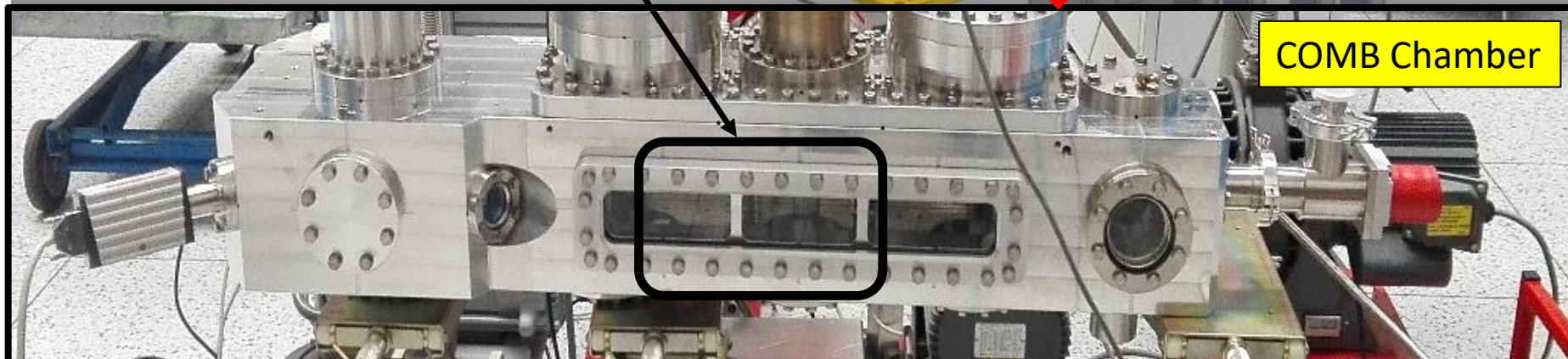
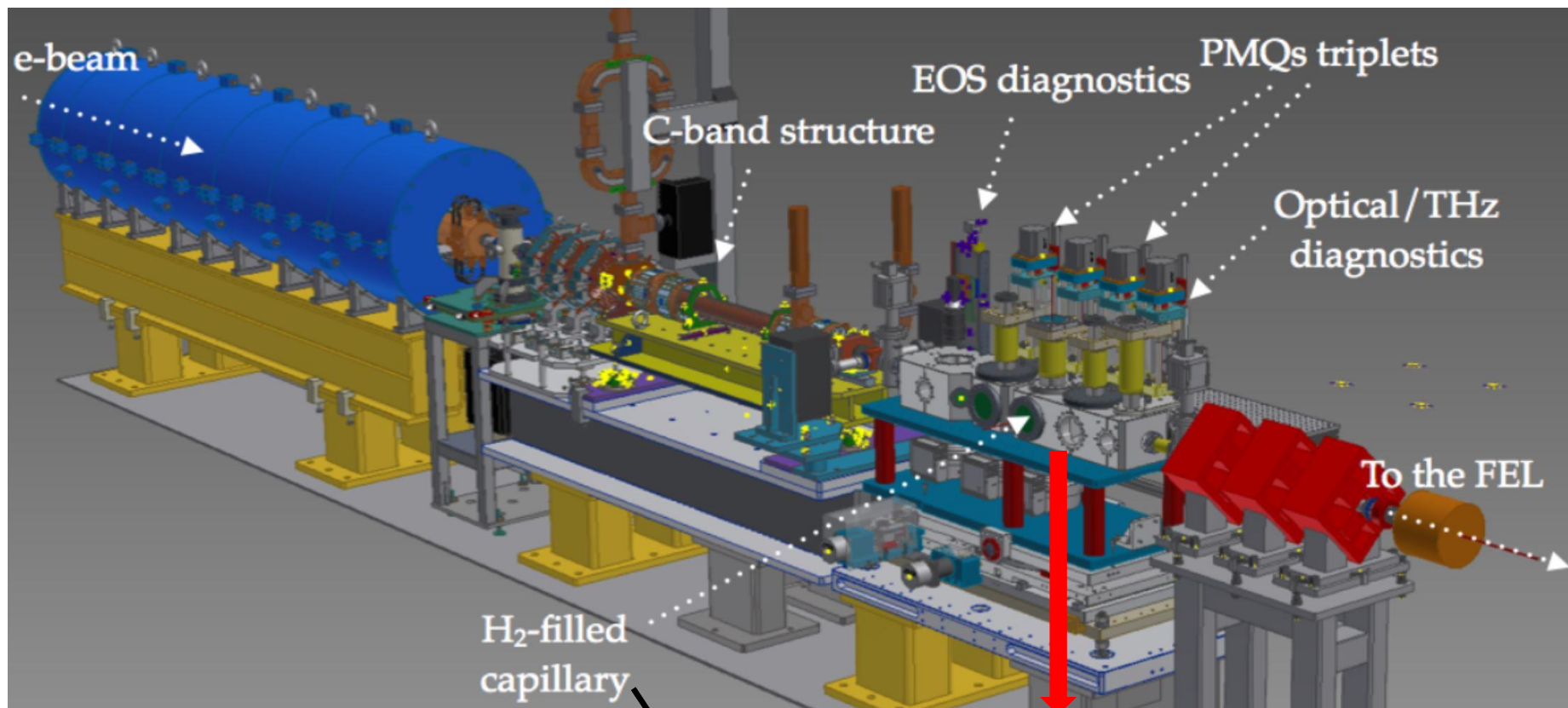
With each Debye length, charges are increasingly electrically screened. Every Debye-length, the electric potential will decrease in magnitude by  $1/e$ .

•**Bulk interactions:** The **Debye length** is much smaller than the physical size of the plasma. This criterion means that interactions in the bulk of the plasma are more important than those at its edges, where boundary effects may take place. When this criterion is satisfied, the plasma is quasineutral.

•**Collisionless:** The electron plasma frequency (measuring plasma oscillations of the electrons) is much larger than the electron–neutral collision frequency. When this condition is valid, electrostatic interactions dominate over the processes of ordinary gas kinetics. Such plasmas are called collisionless.







$$\omega_p = \sqrt{\frac{n_p e^2}{m_e \epsilon_0}}$$

$$\lambda_p = \frac{2\pi c}{\omega_p}$$

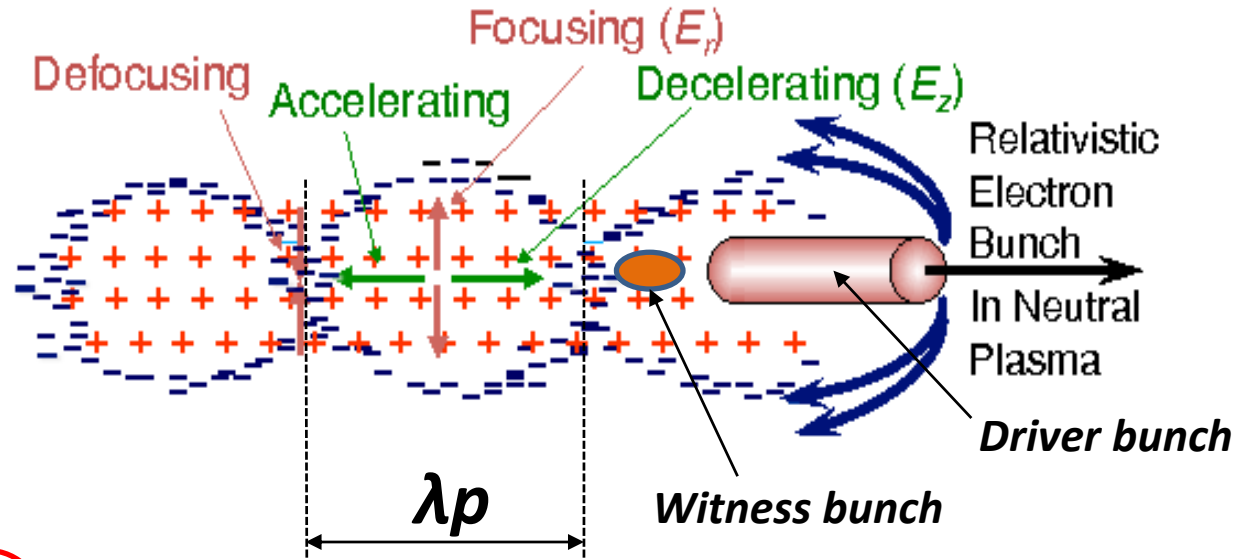
$$E_{cold,wb} [V/m] = \frac{m_e \omega_p c}{e} \approx 96 \sqrt{n_0 [cm^{-3}]}$$

$$\alpha = \frac{n_{bunch}}{n_p}$$

**Linear regime**  $(nb < np)$   
**Weakly NL regime**  $(nb = np)$   
**Non-linear regime**  $(nb \gg np)$

Plasma density measurement represents a crucial point to implement plasma-based devices:

- Accelerators
- Plasma lens



$$n_p = 10^{17} \text{ cm}^{-3}$$

$$\omega_p = 2 \times 10^{13} \text{ Hz}$$

$$E_0 = 30 \frac{\text{GV}}{\text{m}}$$

$$\lambda_p = 100 \text{ } \mu\text{m} \text{ (300 fs)}$$

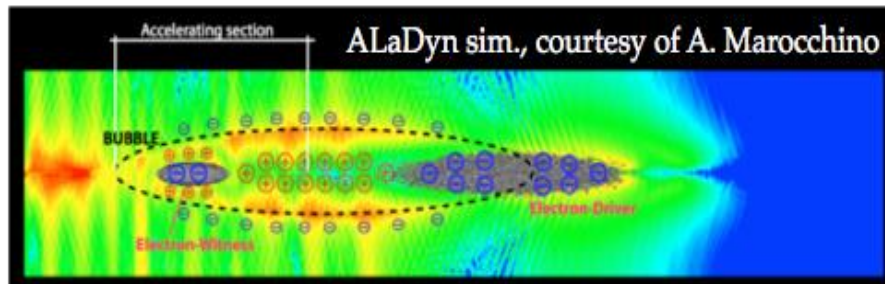
$$\sigma_{zD} \approx 25 \text{ } \mu\text{m} \text{ (75 fs)}$$

$$\sigma_{xD} \approx 2 \text{ } \mu\text{m}$$



**PWFA**

- High quality  $\varepsilon_n \ll 1 \text{ mm mrad}, I_{\text{peak}} \sim \text{kA}, \frac{\Delta\gamma}{\gamma} \ll 1\%$
- External injection of high brightness electron beams



$$n_e = 10^{16} - 10^{18} \text{ cm}^{-3}$$

$$V = 15 - 20 \text{ kV}$$

$$I_{\text{max}} = 50 - 1200 \text{ A}$$

$$R = 1 - 2 \text{ mm}$$

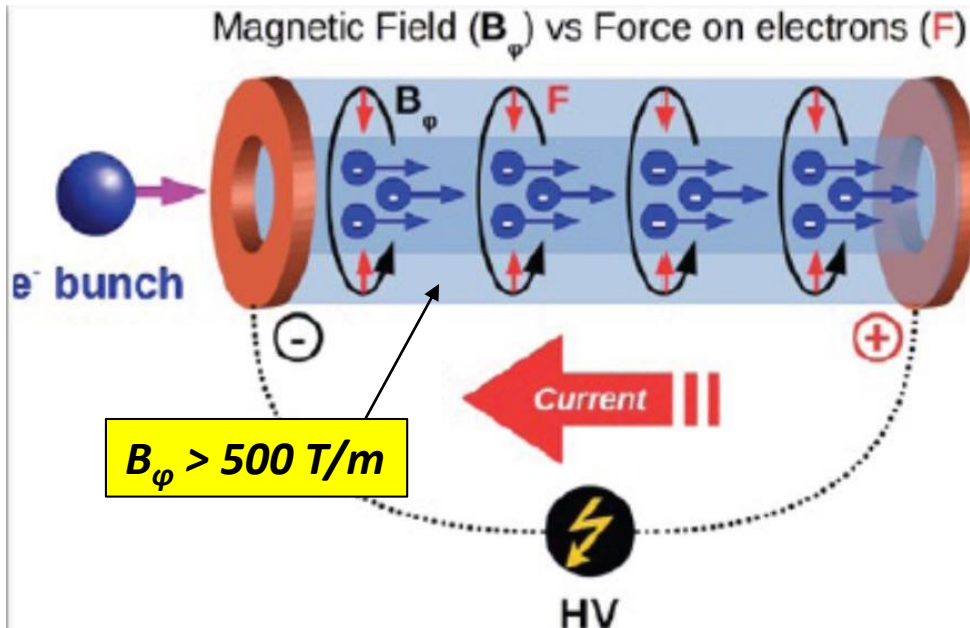
$$L = 1 - 100 \text{ cm}$$

$$\lambda_p (\mu\text{m}) \approx 3.3 \cdot 10^{10} n_p^{-1/2} (\text{cm}^{-3})$$

$$\lambda_p \approx 330 \mu\text{m} @ n_p = 10^{16} \text{ cm}^{-3}$$

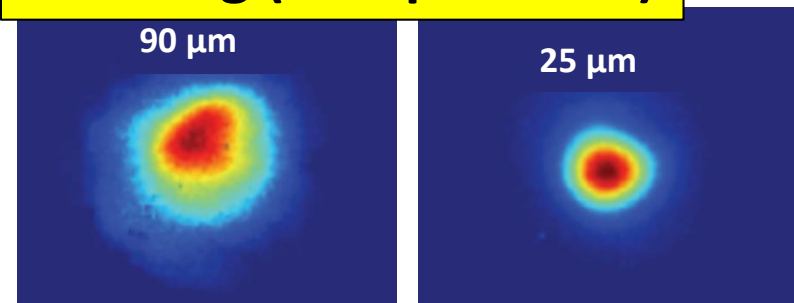
**Plasma lens**

Magnetic Field ( $B_\phi$ ) vs Force on electrons ( $F$ )



$$B_\phi(r) = \frac{\mu_0}{r} \int_0^r J(r') r' dr'$$

$$B_{\text{cost}}(r) = \frac{\mu_0 r i}{2\pi R^2}$$

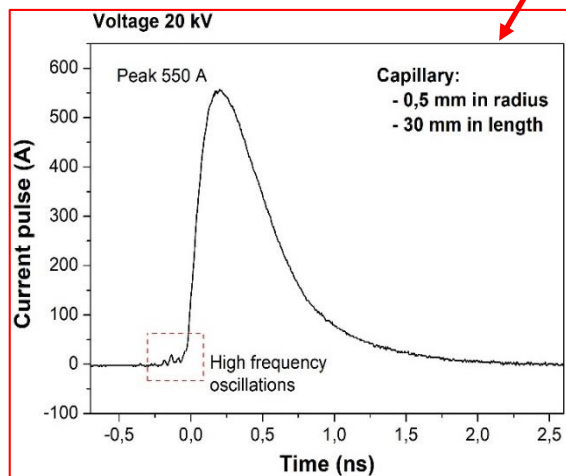
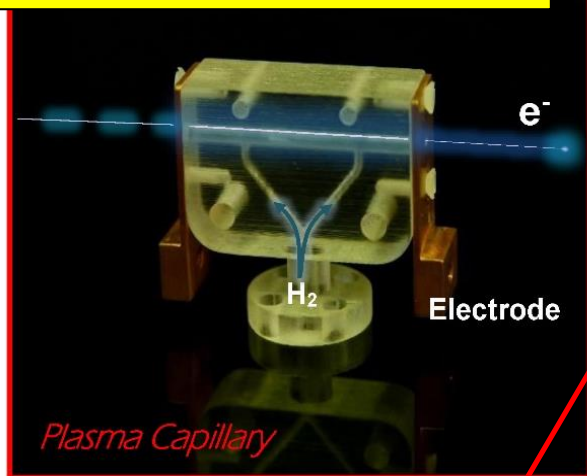
**Focusing (Compactness)**





# Plasma module to confine and produce plasmas

## Plasma source at Sparc\_lab

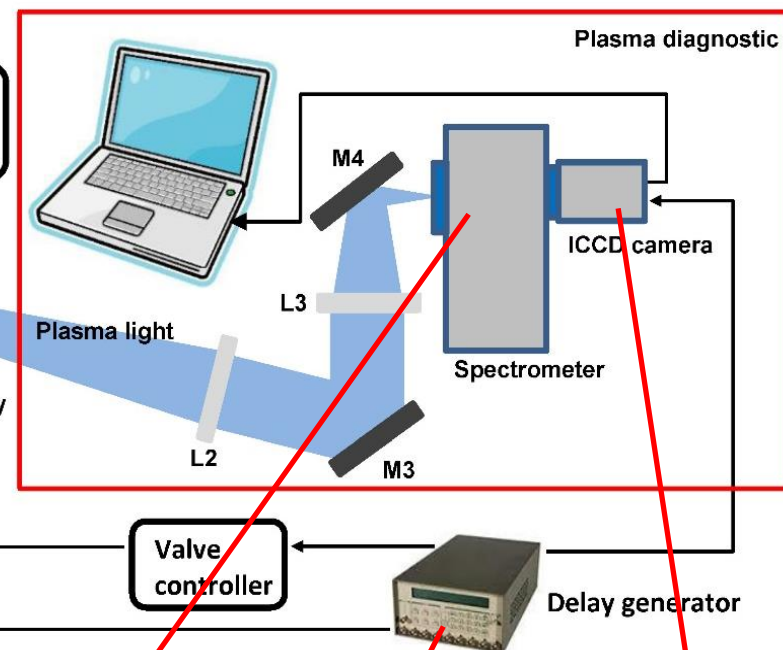


### Capillary shapes:

- Length (Energy)
- Radius (Density)

### Spectrometer:

- Grating
- Optical alignment

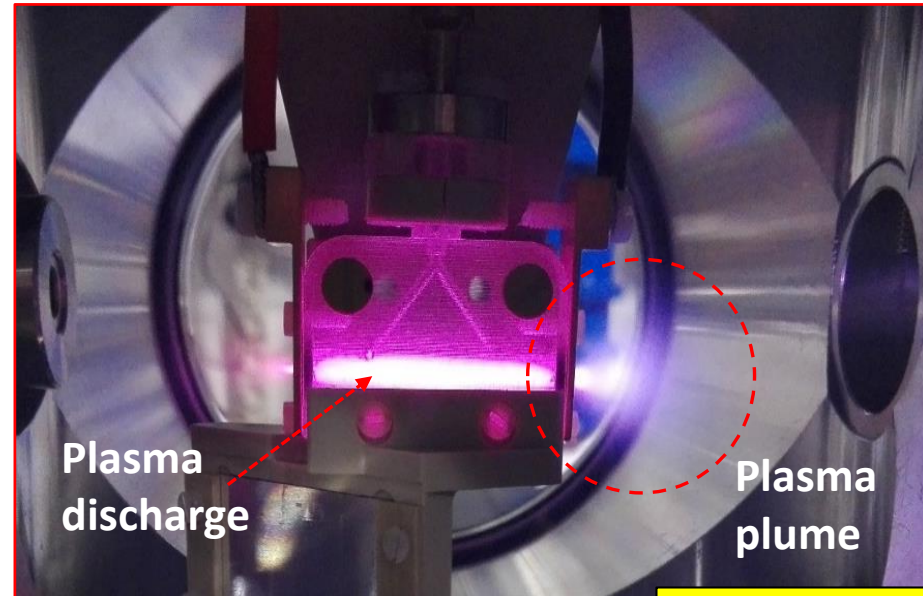
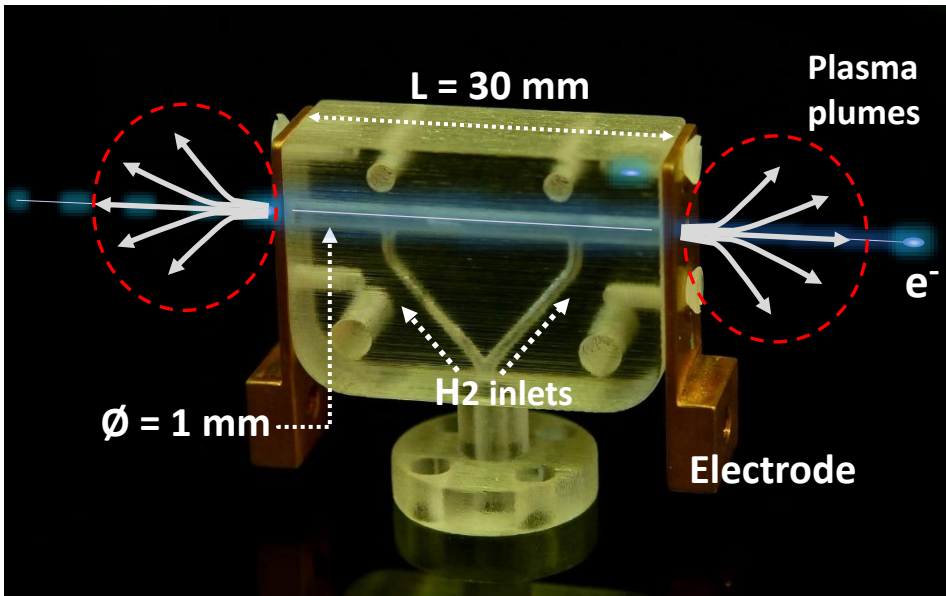


### Timing:

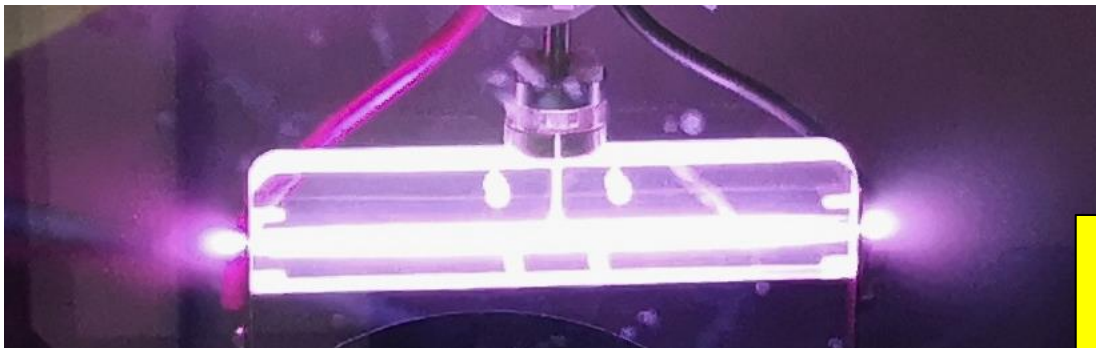
- Valve opening time
- Voltage delay time
- Trigger of ICCD camera

### Camera timing:

- Delay time
- Gate time



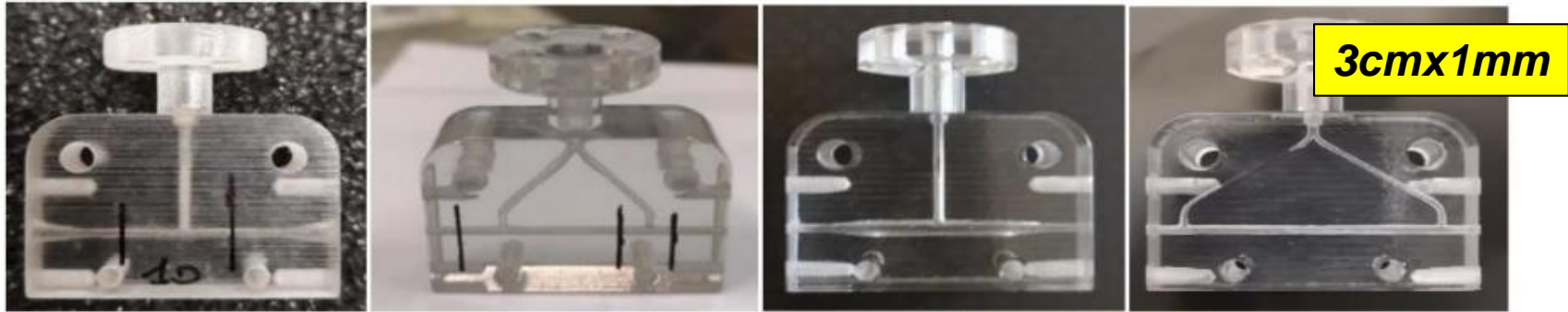
**3cmx1mm  
two inlets**



**10cmx1mm  
single inlet**

- Plasma plumes depend on different conditions of pressure, temperature and density between inside and outside (vacuum) of the capillary
- The expansion velocity and so the plume lengths depends on several terms as the discharge voltage and the geometric properties of the capillary

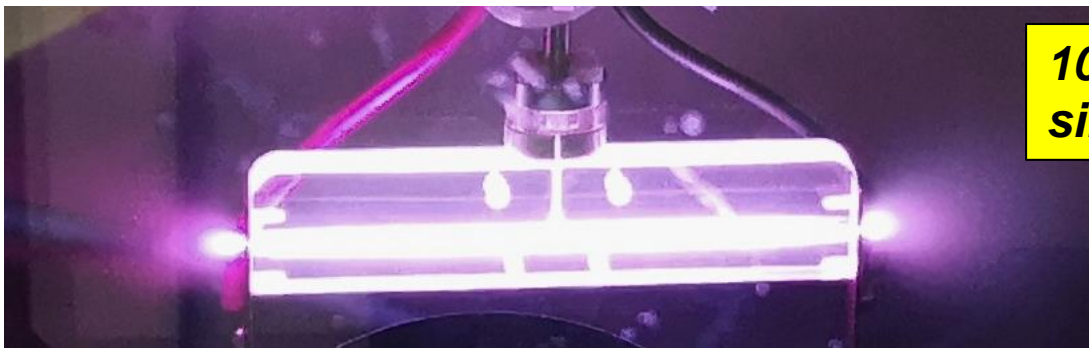
# Plasma sources: gas-filled discharge capillary



**20cmx1mm  
two inlets**



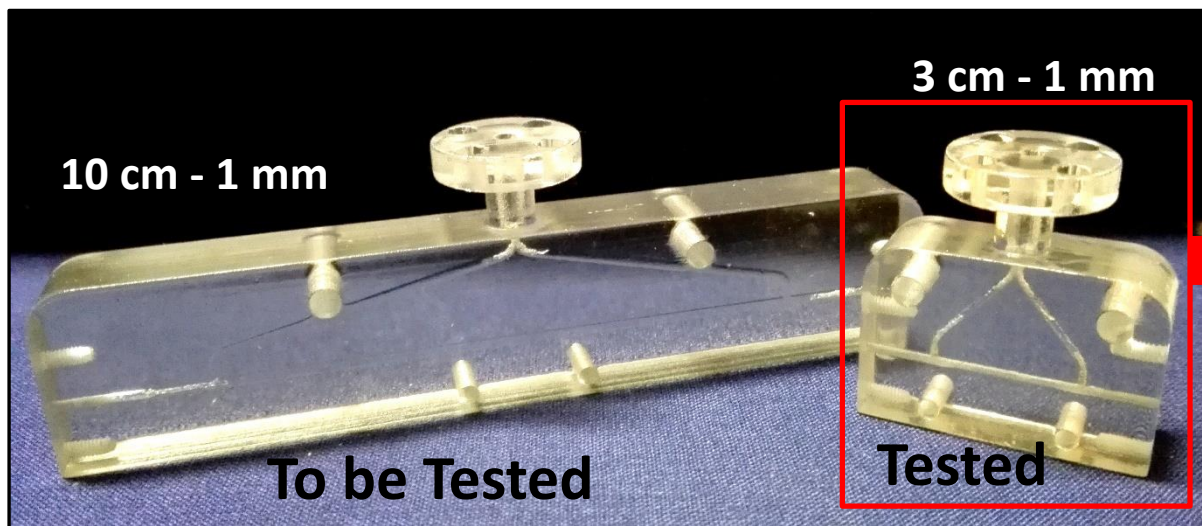
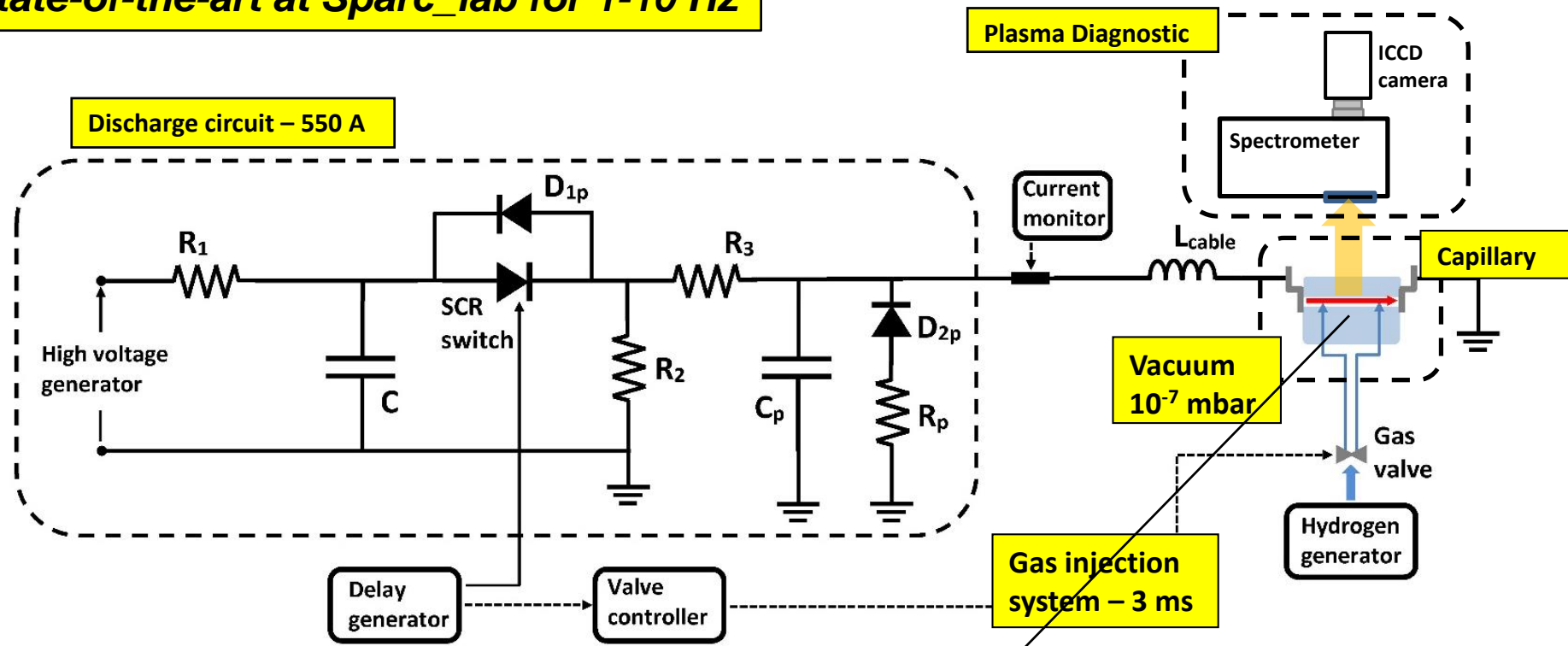
Plasma source characterization means to study the plasma behaviour as a function of many parameters: discharge voltage, position and number of the gas inlets, plasma channel shape and so on, that in turn will affect the quality of the accelerated beam



**10cmx1mm  
single inlet**



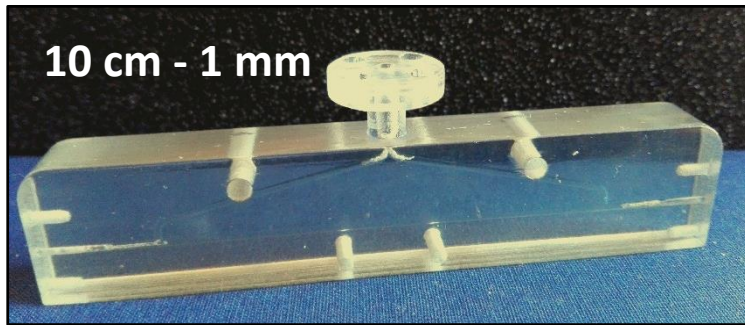
# State-of-the-art at Sparc\_lab for 1-10 Hz



**1-10 Hz**

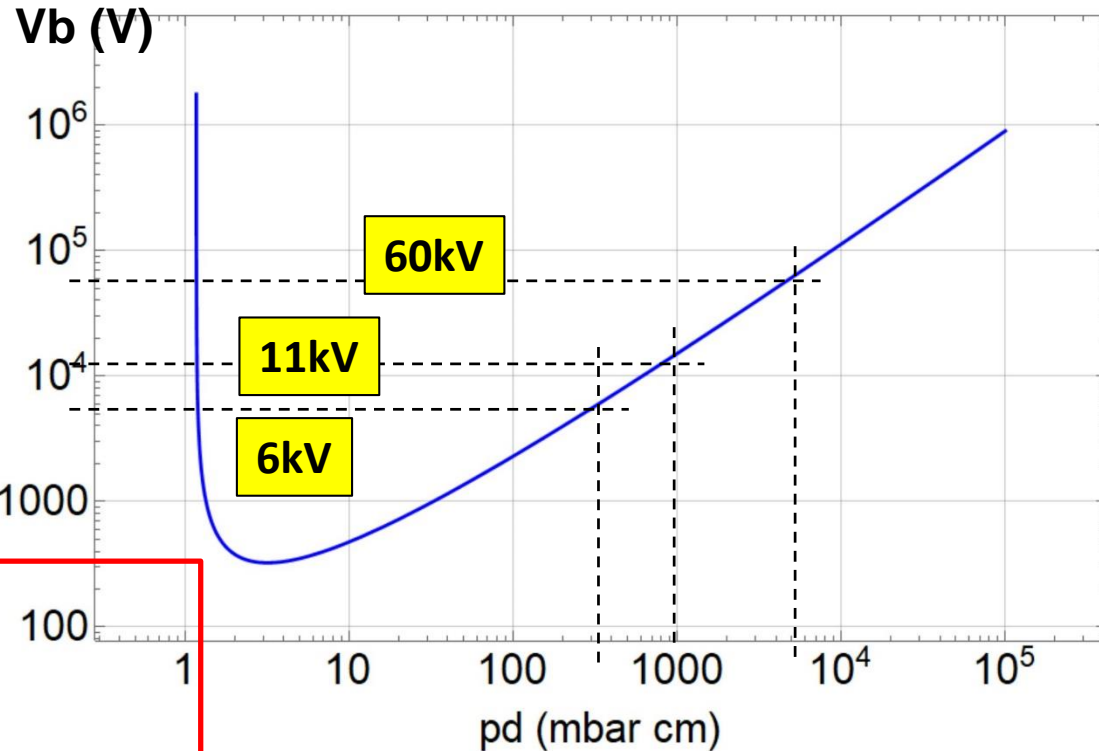
- 3 cm - 1 mm
- 3 cm - 2 mm
- 1 cm - 1 mm
- 2 cm - 1 mm

**Plasma density  
(Stark broadening)  
 $10^{16}$ - $10^{17}$  cm<sup>-3</sup>**



We will start to characterize longer capillary to reach the EuSPARC conditions (PWFA): 40 cm - 1.1 GV/m

Paschen curve H2

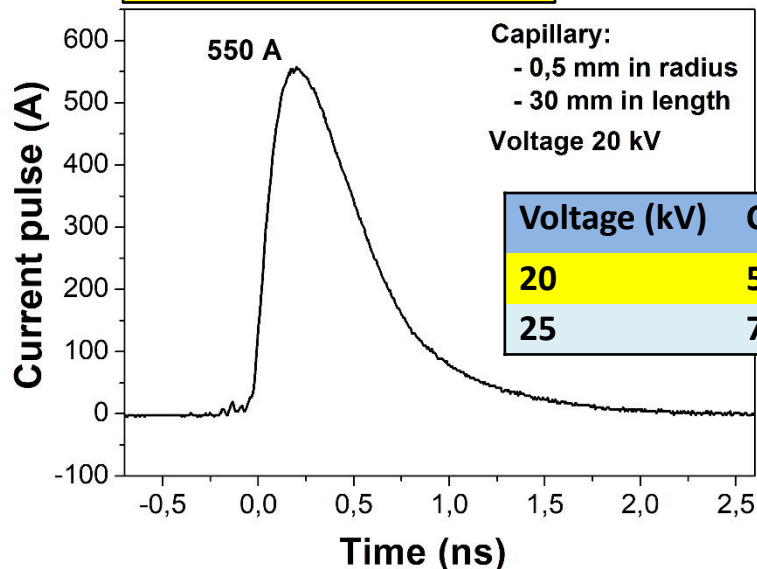


## Vacuum

Parameters: 10 Hz/3 ms

Duration	Vacuum (mbar)
Starting values	$1.3 \times 10^{-9}$
$t_0$	$4.3 \times 10^{-8}$
60 min	$6.4 \times 10^{-8}$ ( $10^{-8}$ )

## Discharge circuit



Voltage (kV)	Current (A)
20	550
25	700

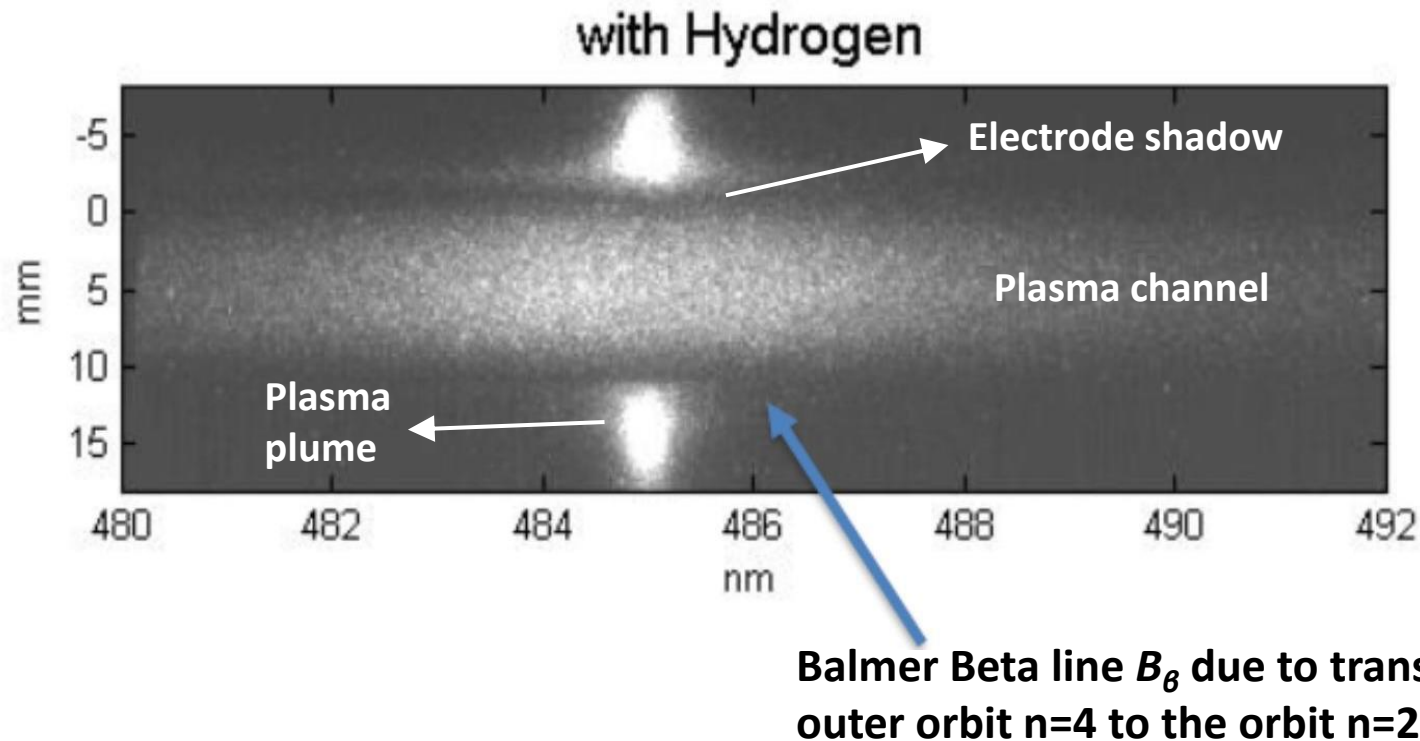
## Gas injection

Capillary	3 cm	10 cm	40 cm
shape	1mm	1mm	1mm
Opening time	5 ms	14 ms	48 ms
Voltage	6 kV	11 kV	60 kV

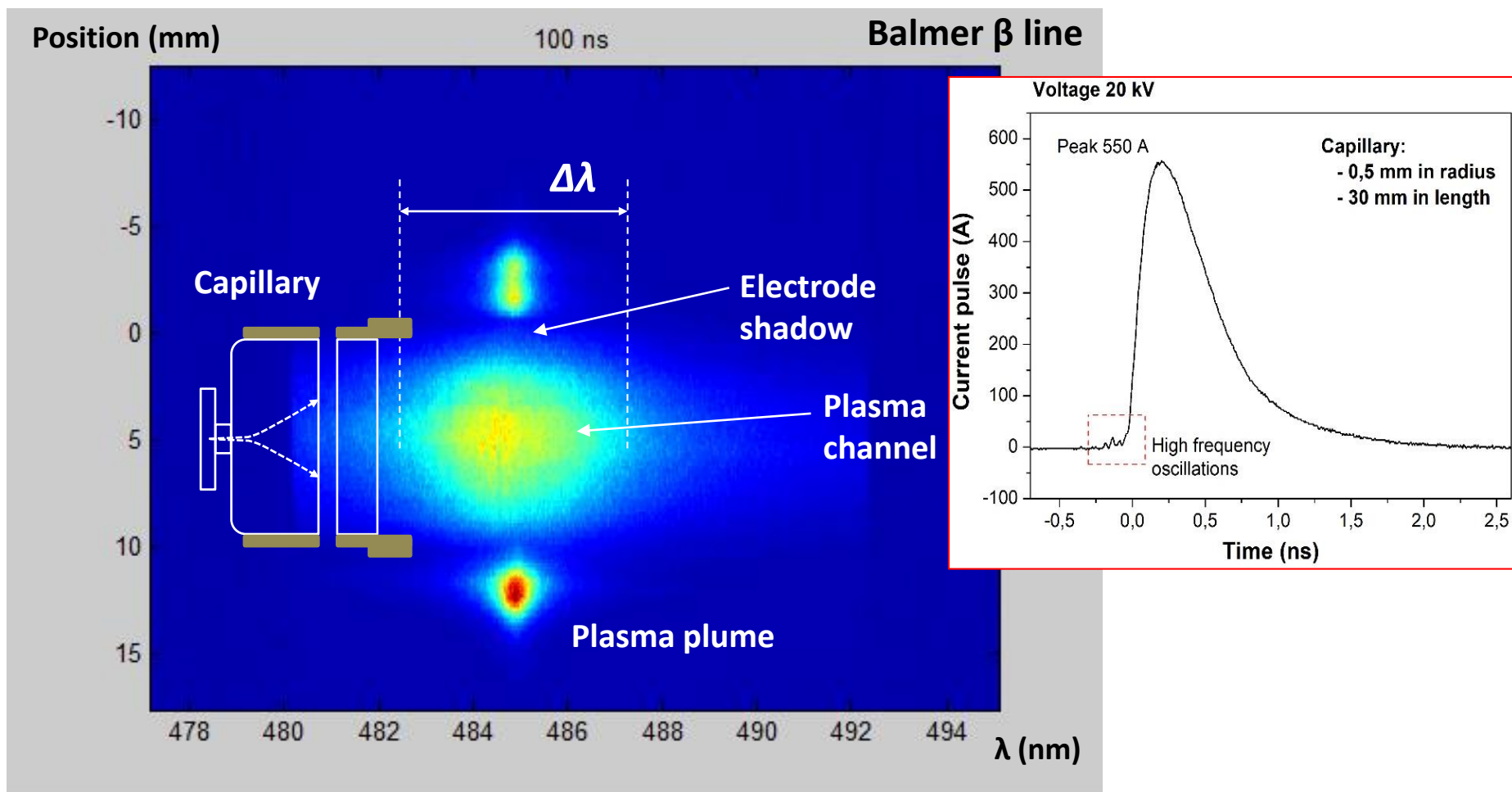
## Stark broadening method

By using the Stark broadening method to measure the plasma density, we obtain the below result: the larger is the Balmer line ( $\Delta\lambda$ ), the higher is the electron density of plasma

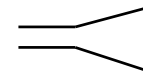
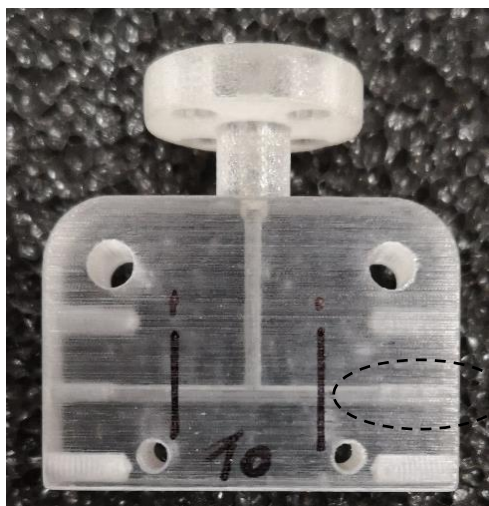
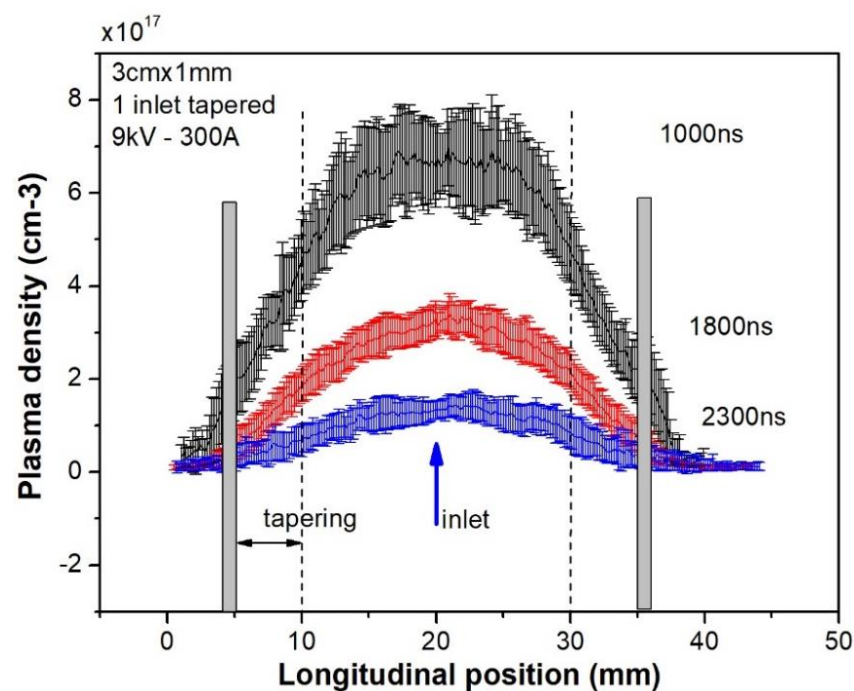
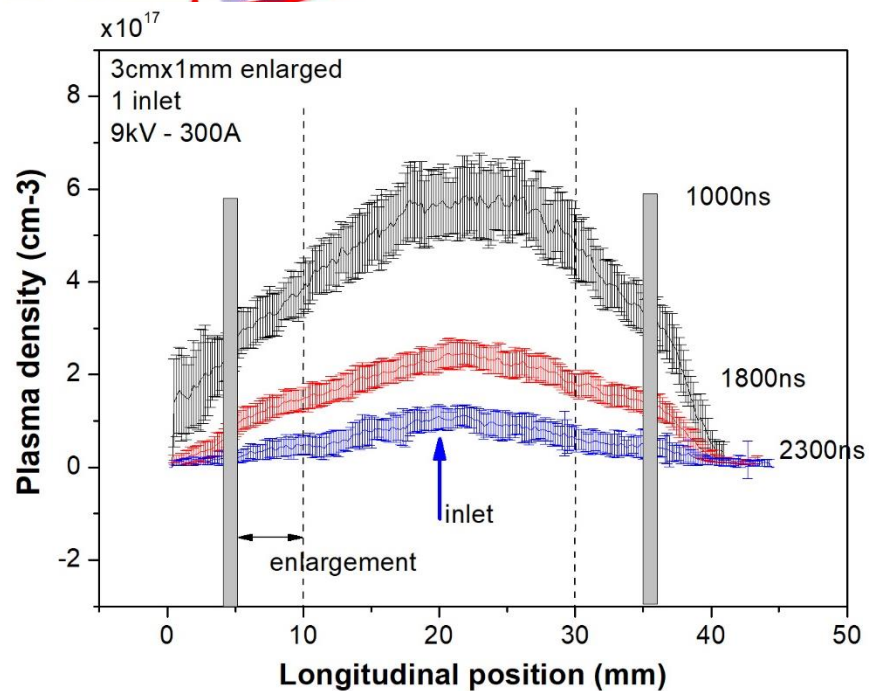
$$n_e = 8.02 \times 10^{12} \left( \frac{\Delta\lambda}{\alpha} \right)^{3/2} \text{ cm}^{-3}$$



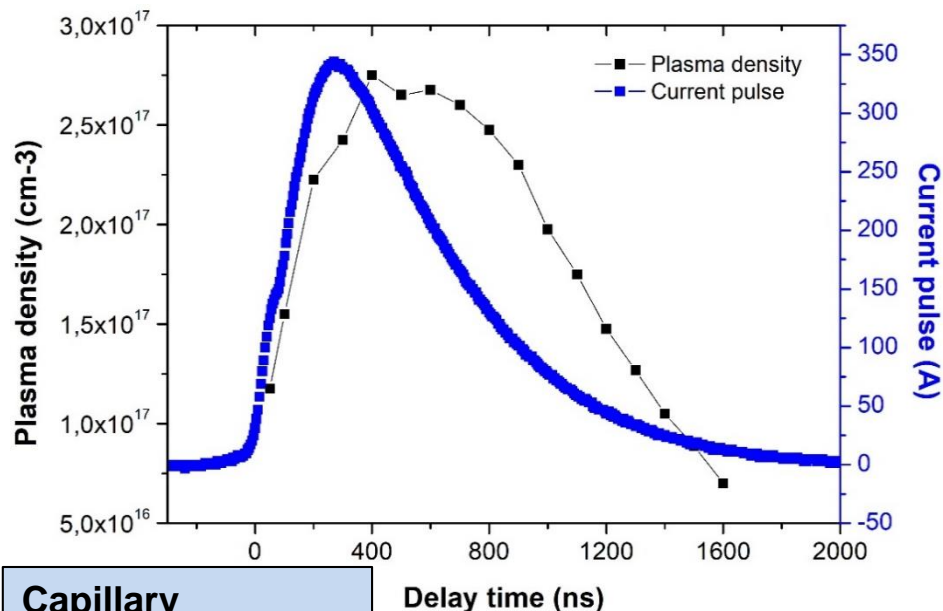
Plasma density inside and outside the capillary will change during the current pulse: such a behaviour it is very important to select when inject the electron bunch



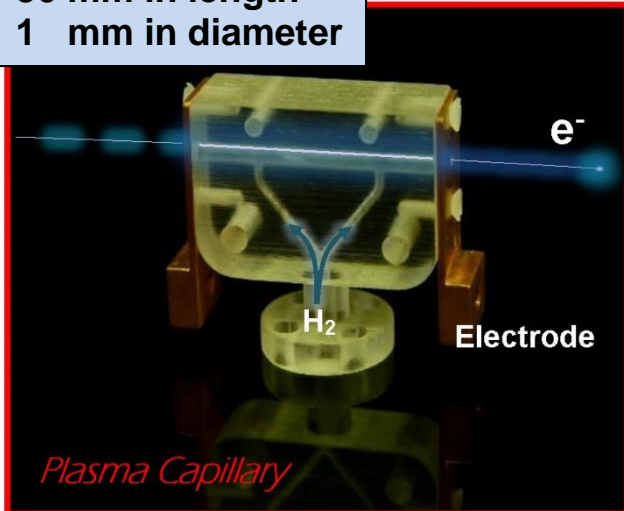




## Time-resolved measures



**Capillary**  
30 mm in length  
1 mm in diameter

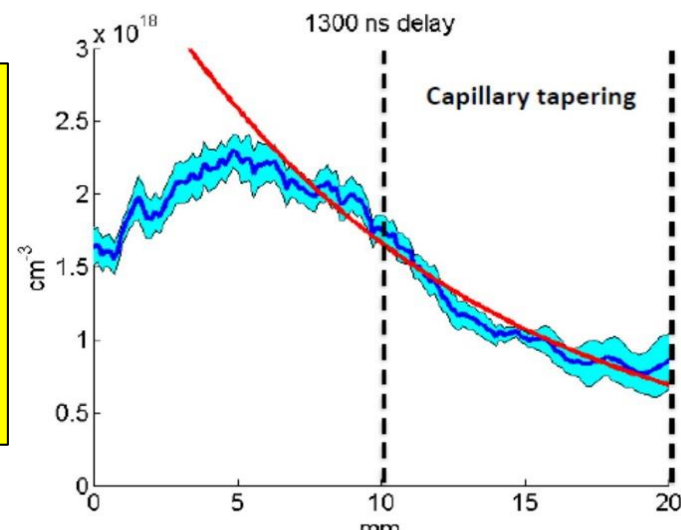
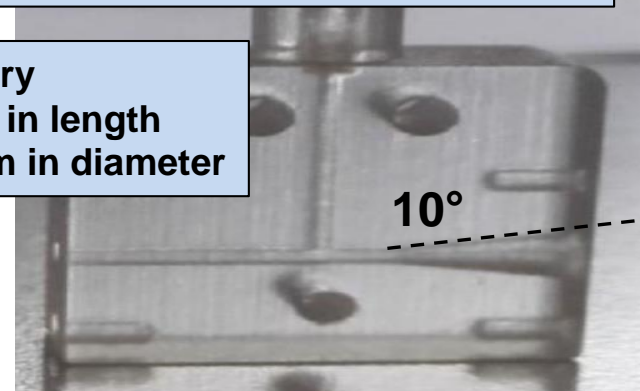


By using the Stark broadening method we measure plasma densities as a function of the delay time from the zero-time of the current pulse and for each one we obtain a longitudinal profile of the density itself

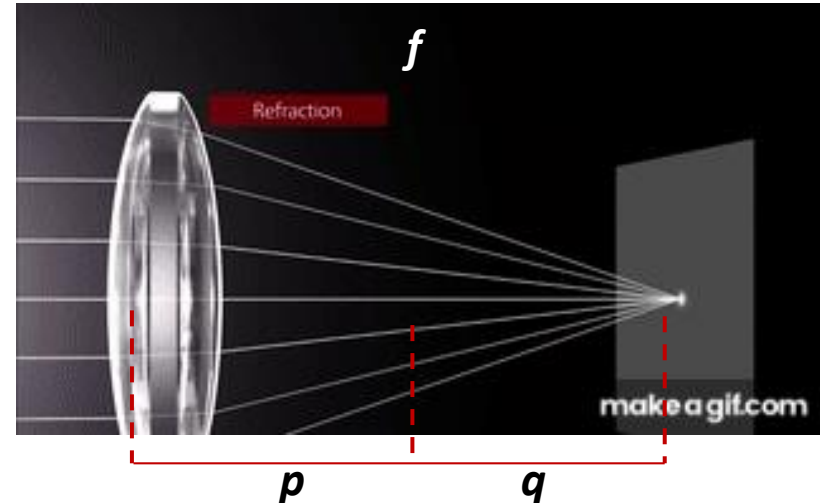
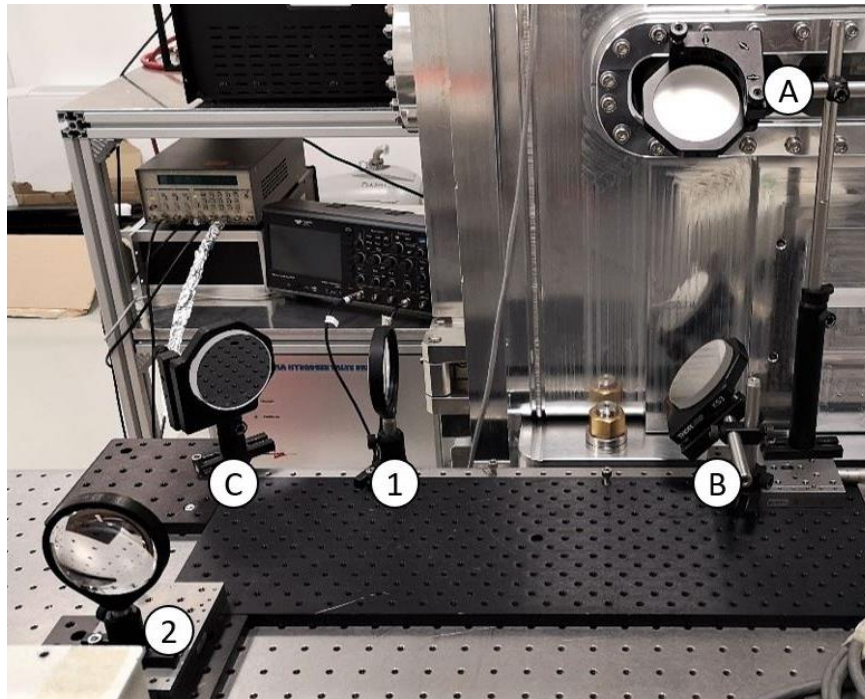
## Space-resolved measures

Tapered capillaries can be used to optimize matching inside the capillary while the beam energy is increasing

Capillary  
30 mm in length  
0.5 mm in diameter



## HOW IS THE CAPILLARY CHARACTERIZED?



- A. Mirror 1
- B. Mirror 2
- C. Mirror 3
- 1. Lens 1
- 2. Lens 2

LENSMAKER'S EQUATION: MAGNIFICATION FACTOR:

$$\frac{1}{f} = \frac{1}{p} + \frac{1}{q}$$

$$M = \frac{q}{p}$$

In case of two lenses, there will be  $p_1$  and  $p_2$ ,  $q_1$  and  $q_2$ ,  $f_1$  and  $f_2$

**Thank you  
for your attention**